

PB 12 SPECIFICATIONS

For Curing Polyimide, BCB, Low-K Dielectrics & Copper Anneal

| SPECIFICATIONS | | | | | | |
|--|---------------|--|---------------|--------------|--|--|
| HARDWARE | | | | | | |
| Clean Room Compatibility | | Class 10 | | | | |
| Chamber Cleanliness | | Class 1 | | | | |
| Wafer Size | | Up to 300 mm | | | | |
| Capacity | | Up to 50 12" wafers/batch (two 25 wafer cassettes) | | | | |
| Operation Temperature | | Ambient to 450°C | | | | |
| N₂ Flow Rate | | 1 SCFM | | | | |
| Nitrogen Consumption | | 15-25 liters/min. | | | | |
| Interior Chamber Dimensions | | 54.34 cm barrel (ID) x 104.06 cm (D) — (21" x 40.97") | | | | |
| Chamber Process Area | | 37.592 cm (W) x 56.64 cm (D) x 36.07 cm (H) — (14.8" x 22.3" x 14.2") | | | | |
| Overall System Dimensions | | 84.48 cm (W) x 174.57 cm (D) x 138.7 cm (H) — (35.23" x 68.73" x 54.61") | | | | |
| Control Console Dimensions | | 59.44 cm (W) x 96.01 cm (D) x 23.62 cm (H) — (23.4" x 37.8" x 9.3") | | | | |
| Chamber Material | | 316L stainless steel | | | | |
| Process Gas Inputs | | 1 standard, up to 3 optional | | | | |
| Mass Flow Controllers | | Optional - up to 3 for gas mixing | | | | |
| Laminar Flow Filter | | 100 micron Mott™ plate filter | | | | |
| Cleanliness | | Particle reduction in most applications | | | | |
| SOFTWARE | | | | | | |
| Number of Recipes | | 8 temperature profiles | | | | |
| Number of Steps for Each Recipe | | 16 program steps | | | | |
| Range of Segment Time | | 0-99 hours | | | | |
| Resolution of Timer Setting | | 1 minute | | | | |
| PERFORMANCE | | | | | | |
| Temperature Uniformity | | ± 7°C during dwell after all temperature points have stabilized for 15 minutes | | | | |
| Average Heat-Up Rate (150°C - 450°C) | | 3.5°C/min. empty chamber, load-dependent | | | | |
| Average Cool-Down Rate (450°C - 150°C) | | 3.0°C/min. empty chamber, load-dependent | | | | |
| Oxygen Concentration | | 10 ppm over background | | | | |
| ADDITIONAL | | | | | | |
| Power Requirements | | 208V, 60 amps, 50/60 Hz, 3 phase | | | | |
| Tool Weight (approx.) | | 894 lbs (406 kgs) | | | | |
| # OF CASSETTES THAT F | IT INSIDE THE | LAMINAR F | LOW ZONE | | | |
| 2 inch wafers | 25 cassettes | | 150 mm wafers | 10 cassettes | | |
| 3 inch wafers | 15 cassettes | | 200 mm wafers | 3 cassettes | | |
| 100 mm wafers | 10 cassettes | | 300 mm wafers | 2 cassettes | | |
| 125 mm wafers | 10 cassettes | | | | | |

Yield Engineering Systems, Inc.

Call: 1-510-954-6889 (worldwide) or 1-888-YES-3637 (US toll free) yieldengineering.com

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PROCESS SOLUTIONS, EQUIPMENT AND SERVICES

PB-Series

Manual Load Vacuum Cure Systems





PB8

Yield Engineering Systems, Inc.

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PB8 SPECIFICATIONS

Y=5°

PB Series

Manual Load Vacuum Cure Systems





PB12: up to 2 cassettes of 300 mm wafers

PB8: up to 2 cassettes of 200 mm wafers

The YES-PB Series is the result of decades of experience in the design and manufacture of low particle ovens. These dependable systems provide complete removal of residual solvents, uniform temperature distribution, pressure control, a dry inert atmosphere, and precise management of heating and cooling rates.

The Vacuum Cure Advantage

- Faster process: 3.5 hours vs 8+ hours
- Laminar flow reduces/eliminates particles
- More complete cure (5x less outgassing)
- Less film stress and low wafer warpage
- 1.6x to 2x less power and N_2 consumption
- Much lower capital cost, 2-3x lower CoO

COMMON APPLICATIONS

Polyimide and BCB cure

Copper anneal

Aluminum anneal

Contact Us: We offer process demonstrations. If you would like to submit samples, please call us. We can run your samples and provide a detailed process report.

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yieldengineering.com

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| | | SPECIFIC | ATIONS | |
|--|---------------|---|---------------|-------------|
| HARDWARE | | | | |
| Clean Room Compatibility | | Class 10 | | |
| Chamber Cleanliness | | Class 1 | | |
| Wafer Size | | Up to 200 mm | | |
| Capacity | | Up to 50 8" wafers/batch (two 25 wafer cassettes) | | |
| Operation Temperature | | Ambient to 450°C | | |
| N₂ Flow Rate | | 1 SCFM | | |
| Nitrogen Consumption | | 15-25 liters/min. | | |
| Interior Chamber Dimensions | | 36.62 cm barrel (ID) x 66.52 cm (D) — (14.42" x 26.19") | | |
| Chamber Process Area | | 23.95 cm (W) x 45.97 cm (D) x 24.69 cm (H) — (9.43" x 18.10" x 9.72") | | |
| Overall System Dimensions | | 68.96 cm (W) x 145.92 cm (D) x 77.87 cm (H) — (27.15" x 57.45" x 30.64") | | |
| Control Console Dimensions | | 59.44 cm (W) x 96.01 cm (D) x 23.62 cm (H) — (23.4" x 37.8" x 9.3") | | |
| Chamber Material | | 316L stainless steel | | |
| Process Gas Inputs | | 1 standard, up to 3 optional | | |
| Mass Flow Controllers | | Optional - up to 3 for gas mixing | | |
| Laminar Flow Filter | | 100 micron Mott™ plate filter | | |
| Cleanliness | | Particle reduction in most applications | | |
| SOFTWARE | | | | |
| Number of Recipes | | 8 temperature profiles | | |
| Number of Steps for Each Recipe | | 16 program steps | | |
| Range of Segment Time | | 0-99 hours | | |
| Resolution of Timer Setting | | 1 minute | | |
| PERFORMANCE | | | | |
| Temperature Uniformity | | ± 5°C during dwell after all temperature points have stabilized for 15 minute | | |
| Average Heat-Up Rate (150°C - 450°C) | | 5°C/min. empty chamber, load-dependent | | |
| Average Cool-Down Rate (450°C - 150°C) | | 4°C/min. empty chamber, load-dependent | | |
| Oxygen Concentration | | 10 ppm over background | | |
| ADDITIONAL | | | | |
| Power Requirements | | 208V, 40 amps, 50/60 Hz, 3 phase | | |
| Tool Weight (approx.) | | 575 lbs (261 kgs) | | |
| # OF CASSETTES THAT F | IT INSIDE THE | LAMINAR FI | LOW ZONE | |
| 2 inch wafers | 9 cassettes | | 150 mm wafers | 3 cassettes |
| 3 inch wafers | 6 cassettes | | 200 mm wafers | 2 cassettes |
| 100 mm wafers | 3 cassettes | | 300 mm wafers | 0 cassettes |
| 125 mm wafers | 3 cassettes | | | |

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Tool temperature performance is a combination of temperature control accuracy and temperature uniformity. Accuracy is the deviation of the average product temperature from the set point. Uniformity is the deviation between the maximum and minimum product temperatures and is not related to the set point. Accuracy is calculated as set point – average temperature. Uniformity is calculated as (maxmin)/(max+min). YES-PB series tools have dwell accuracy of +/-1.5°C after stabilization. After stabilizing at dwell, all product temperatures should be within 10°C or 14°C of each other (depending on the tool) and within 7°C or 8.5°C of set point (depending on the tool).